

0.5 μm MESFET – PE Foundry Process

DESCRIPTION

The PE process utilizes molecular beam epitaxy (MBE) to implement a MESFET active layer structure that achieves high breakdown and high efficiency for multi-watt power applications thru 18 GHz. Wafer diameter is 100 mm. The focus is on products for moderate to high volume applications. MACOM offers a full range of foundry services to meet the requirements for custom designing a MMIC-based die or packaged product. The linearity on this MESFET process is higher than traditional pHEMT processes.

FEATURES

- High Breakdown Voltage
- High Efficiency
- Excellent Linearity

APPLICATIONS

- High Power Amplifiers and Driver Amplifiers for Applications up to 15 GHz
- VSAT Power Amplifiers
- High Efficiency Power Amplifiers

PERFORMANCE SUMMARY

Parameter	Test Conditions	Units	Typical
MAG	$V_{DS} = 8\text{ V}$, $I_{DS} = 40\% I_{DSS}$ 2 GHz 12 GHz	dB	22.0 13.5
P @ 1 dBc	$V_{DS} = 8\text{ V}$, $I_{DS} = 40\% I_{DSS}$ 2 GHz 12 GHz	mW/mm	680 525
PAE	$V_{DS} = 8\text{ V}$, $I_{DS} = 40\% I_{DSS}$ 2 GHz 12 GHz	%	50 41
FT	$V_{DS} = 8\text{ V}$, $I_{DS} = 40\% I_{DSS}$	GHz	20
MTTF	$V_{DS} = 9.5\text{ V}$, $I_{DS} = 50\% I_{DSS}$, $T_{CH} = 125\text{ }^{\circ}\text{C}$	Hours	3×10^6

0.5 μm MESFET – PE Foundry Process (continued)ELECTRICAL SPECIFICATIONS: $T_A = +25\text{ }^\circ\text{C}$

Parameter	Test Conditions	Units	Min.	Typ.	Max.
200 μm PCM FET					
I_{DSS}	$V_{DS} = 3\text{ V}, V_{GS} = 0\text{ V}$	mA/mm	190	240	270
DC GM	$V_{DS} = 3\text{ V}, I_{DS} = 50\% I_{DSS}$	mS/mm	145	150	185
V_p	$V_{DS} = 3\text{ V}, I_{DS} = 2.5\% I_{DSS}$	V	-1.3	-1.8	-2.2
BV_{gd}	$I_G = 1\text{ mA/mm}$	V	-11	-15	—
F_t	$V_{DS} = 3\text{ V}, I_{DS} = 50\% I_{DSS}$	GHz	20	26	34
Sheet Resistances					
NDRS (N-GaAs)	$I = 20\text{ mA}$	Ω/sq	340	375	410
NCRS (NiCr)	$I = 10\text{ mA}$	Ω/sq	40	50	60
MIM Capacitors					
Capacitance/Unit Area	$f = 1\text{ MHz}$	pF/mm^2	360	400	440
Capacitor Leakage	$V = 10\text{ V}$	μA	—	—	0.5

0.5 μm MESFET – PE Foundry Process (continued)

BENEFITS OF USING MACOM AS A FOUNDRY SERVICE:

- Over 17 years of GaAs MMIC production experience
- A complete offering of stable and mature GaAs production processes for commercial handset, infrastructure, and military applications
- Superior device performance to meet the most stringent specifications
- World-class testing and modeling capabilities
- Shortest production cycle time in the industry
- Proven manufacturer of microwave components and systems for more than 50 years

MACOM FOUNDRY SERVICES INCLUDE::

- Support in:
 - Layout
 - DRC and LVS Checking
 - Technical Consultation
- Provide Design Kit including Transistor Models and Passive Models to Assist Design

FOUNDRY SERVICES AVAILABLE UPON REQUEST:

- Extract Small Signal, Noise, and Large Signal Models
- Provide Transistor Characterization Data in:
 - Small Signal Measurements
 - Load Pull Measurements
- Perform Circuit Test at:
 - Wafer Level
 - Package Level
- Production Qualification Testing